20th Anniversary of KSDT

KISM 2022

Korean International Semiconductor Conference on Manufacturing Technology 2022

November 13-16, 2022 | Paradise Hotel Busan (Haeundae Beach), Busan, Korea

Session Title:	[TD1] EUV Resist Ⅱ and Alternative Lithography
Session Date:	November 15 (Tue.), 2022
Session Time:	09:30-10:50
Session Room:	Room D (Sidney Room, 2F)
Session Chair:	Prof. Seokwoo Jeon (KAIST, Korea)

[TD1-1] 09:30-09:50

Underlayer Materials for Challenges of Advanced Patterning Process

Jae Hwan Sim, Jung-June Lee, Soojung Leem, Jae Yun Ahn, Joo Sung Lee, Min Young Jeong, and Youngeun Bae (DuPont Electronics & Industrial, Korea)

[TD1-2] 09:50-10:10

Design of Novel Tin Oxo Clusters for EUV Photoresist

Hyun-Dam Jeong (Chonnam Nat'l Univ., Korea)

[TD1-3] 10:10-10:30

Nanoimprinted Meta-Surface (Meta-Lens)

Heon Lee (Korea Univ., Korea)

[TD1-4] 10:30-10:50

Photolithographic Realization of Target Nanostructures in 3D Space for Semiconducting Applications via Inverse Design of Phase Modulation

Seokwoo Jeon (KAIST, Korea)